

Amendments to the Claims:

This listing of claims replaces all prior versions and listings of claims in the application:

Listing of Claims:

1. (Currently Amended) A method comprising:  
forming a first electrode and a second electrode on a base body; [[and]]  
chemically etching at least a portion of the base body to adjust a resistance of the base  
body between the first electrode and the second electrode; and  
measuring a resistance of the base body while chemically etching the at least a portion of  
the base body.
2. (Original) The method of claim 1, wherein the base body comprises a ceramic  
material.
3. (Original) The method of claim 1, wherein the base body comprises a material  
having a resistance with a negative temperature coefficient.
4. (Original) The method of claim 1, wherein a length of an edge of the base body is  
less than about 3 mm.

5. (Original) The method of claim 1, wherein chemically etching at least a portion of the base body comprises immersing the base body in an etching liquid.

6. (Original) The method of claim 5, wherein the etching liquid comprises sulfuric acid.

7. (Original) The method of claim 1, further comprising measuring a value of a resistance of the base body prior to chemically etching the at least a portion of the base body.

8. (Canceled)

9. (Original) The method of claim 1, further comprising:  
determining a difference between the predetermined value and a measured value of the resistance; and

determining a duration for the chemically etching based on said difference, wherein chemically etching at least a portion of the base body comprises chemically etching at least a portion of the base body for the duration.

10. (Original) The method of claim 1, wherein forming the first electrode and the second electrode on the base body comprises forming the first electrode at a location opposite the second electrode on the base body.

11. (Original) The method of claim 1, wherein chemically etching at least a portion of the base body to adjust the resistance of the base body comprises chemically etching at least a portion of the base body to adjust the resistance of the base body to a predetermined value.